L Number	Hits	Search Text	DB	Time stamp
1	670		USPAT;	2002/09/30 13:44
5	23		EPO; JPO USPAT;	2002/09/30 13:45
3	23	((reactant reactive source) adj3 gas\$2)	EPO; JPO	
_	388700	•	USPAT	2002/09/27 13:47
_	970227	1 2 2	USPAT	2002/03/02 16:26
	330656	"dihydrogen oxide" "Hydrogen oxide" Water  (argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide"  "Nitrogen oxide" "Mononitrogen" monoxide	USPAT	2002/03/02 16:26
		"Nitric oxide"  "Nitrous Oxide"  "dinitrogen monoxide" "hyponitrous acid"  "anhydride Nitrogen Oxide" "Dinitrogen oxide"  "dihydrogen oxide" "Hydrogen oxide" Water		
	,	)	пораш	2002/03/02 16:27
	2983	((argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide" "Nitrogen oxide" "Mononitrogen" monoxide "Nitric oxide" "Nitrous Oxide" "dinitrogen monoxide" "hyponitrous acid" "anhydride Nitrogen Oxide" "Dinitrogen oxide"	USPAT	2002/03/02 10.27
	2983	"dihydrogen oxide" "Hydrogen oxide" Water )) and "vacuum pressure" (((argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide" "Nitrogen oxide" "Mononitrogen" monoxide "Nitric oxide" "Nitrous Oxide" "dinitrogen monoxide" "hyponitrous acid" "anhydride Nitrogen Oxide" "Dinitrogen	USPAT	2002/03/02 16:35
	13	oxide"  "dihydrogen oxide" "Hydrogen oxide" Water )) and "vacuum pressure") and vacuum ((((argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide" "Nitrogen oxide" "Mononitrogen" monoxide "Nitric oxide" "Nitrous Oxide"	USPAT	2002/03/02 16:28
		"dinitrogen monoxide" "hyponitrous acid" "anhydride Nitrogen Oxide" "Dinitrogen oxide"  "dihydrogen oxide" "Hydrogen oxide" Water )) and "vacuum pressure") and vacuum) and (dilut\$3 near nitrogen)		

	F25020			10000100100
	535039	((((argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide" "Nitrogen oxide" "Mononitrogen" monoxide "Nitric oxide" "Nitrous Oxide" "dinitrogen monoxide" "hyponitrous acid" "anhydride Nitrogen Oxide" "Dinitrogen oxide"	USPAT	2002/03/02 16:33
	354	"dihydrogen oxide" "Hydrogen oxide" Water )) and "vacuum pressure") and vacuum) and ultra thin (((argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide" "Nitrogen oxide" "Mononitrogen" monoxide "Nitric oxide" "Nitrous Oxide" "dinitrogen monoxide" "hyponitrous acid" "anhydride Nitrogen Oxide" "Dinitrogen oxide"	USPAT	2002/03/02 16:34
	59	"dihydrogen oxide" "Hydrogen oxide" Water )) and "vacuum pressure") and vacuum and ultra (((argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide" "Nitrogen oxide" "Mononitrogen" monoxide "Nitric oxide" "Nitrous Oxide" "dinitrogen monoxide" "hyponitrous acid" "anhydride Nitrogen Oxide" "Dinitrogen oxide"	USPAT	2002/03/02 16:35
	57	"dihydrogen oxide" "Hydrogen oxide" Water )) and "vacuum pressure") and vacuum and LPCVD ((((argon helium nitrogen) and (oxygen ammonia TaETO "nitrogen monoxide" "Nitrogen oxide" "Mononitrogen" monoxide "Nitric oxide" "Nitrous Oxide" "dinitrogen monoxide" "hyponitrous acid" "anhydride Nitrogen Oxide" "Dinitrogen oxide"	USPAT	2002/03/02 16:35
	2149	"dihydrogen oxide" "Hydrogen oxide" Water )) and "vacuum pressure") and vacuum and LPCVD) and temperature unload\$3 near (wafer substrate semiconductor)	USPAT; US-PGPUB; EPO; JPO	2002/09/27 13:50
_	1148	(unload\$3 near (wafer substrate semiconductor)) and temperature	USPAT; US-PGPUB;	2002/09/27 13:51
_	50	((unload\$3 near (wafer substrate semiconductor)) and temperature) and	EPO; JPO USPAT; US-PGPUB;	2002/09/27 15:02
_	308	((steady adj3 state) "steady state") cluster adj2 tools	EPO; JPO USPAT; US-PGPUB;	2002/09/27 15:03
_	120	(cluster adj2 tools) and cooling	EPO; JPO USPAT; US-PGPUB;	2002/09/27 15:25
_	175	bonderer.xa.	EPO; JPO USPAT; US-PGPUB;	2002/09/27 15:26
_	157	kilday.xa.	EPO; JPO USPAT; US-PGPUB; EPO; JPO	2002/09/27 15:42